

Mega-Etch Filter

LENNTECH

info@lennotech.com

www.lennotech.com

Tel. +31-15-261.09.00

Fax. +31-15-261.62.89



Description

The Mega-Etch filter is targeted for use in recirculating etch baths. Utilizing our patented asymmetric polysulfone membrane enables the Mega-Etch filter to provide the following benefits:

- Available in retention ratings of 0.05, 0.1, 0.2, 0.45 μm
- High flow vs. low-pressure drop
- No pre-wetting with IPA required
- Fast bath clean-up • Patented highly asymmetric polysulfone membrane assures long life

Specifications

Materials

- Medium: Highly asymmetric hydrophilic polysulfone
- Hardware: Polypropylene
- Support: Polypropylene
- O-ring: Viton¹ A (standard)

Removal Ratings

- 0.45 μm (0.1 μm RP²), 0.2 μm , 0.1 μm , 0.05 μm

Filter Areas

- 10" / 254 mm - 7.0 ft.² / 0.65 m²
- 20" / 508 mm - 14.0 ft.² / 1.30 m²

Configurations

- Nominal Length:
10" / 25.4 cm, 20" / 50.8 cm
- Diameter 2.6" / 6.6 cm

Operating Conditions

Maximum Operating Temperature:

- 203°F / 95°C

Maximum Forward Differential Pressure:

- 50 psid @ 60°F / 3.45 bar @ 20°C

Performance Parameters

Mega-Etch cartridges are available in single pass ratings of 0.05, 0.1, 0.2, or 0.45 μm . In addition, the Mega-Etch 0.45 (EBC450) cartridge has a Recirculating Performance of 0.1 μm^2 .

Target Applications

The Mega-Etch cartridge is used as the primary filter in recirculating etch baths. When operated at ambient temperature, it is compatible with a wide variety of etch solutions.²

The Mega-Etch cartridge is highly recommended for use in SiO₂ Etch with surfactant and low horsepower internal pumps.

The Mega-Etch cartridge will pressure wet when used in SiO₂ Etch without surfactant and with higher horsepower pumps, or use the Pall Ulti-Etch™ Filter for spontaneous wetting in high surface tension fluids.

The Mega-Etch cartridge is recommended for use in semi-aqueous strippers that are primarily HF based.²

¹ Viton is a trademark of DuPont Dow Elastomers

² Recirculating Performance. See Technical Bulletin 1038-T for more information.

³ Before installation, the Mega-Etch cartridge should be tested to determine compatibility

Part Numbers / Ordering Information

EBC



EBC Etch Bath Cartridge

Code	Removal Ratings in Microns (μm)	Code	Cartridge Lengths
050	0.05	10	10" / 254 mm
100	0.1	20	20" / 508 mm
200	0.2		
450	0.45 (0.1 RP ²)		

Code End Configurations

M3	SOE flat closed end, external 222 O-rings
M7	SOE fin end, external 226 O-rings
M8	SOE fin end, external 222 O-rings

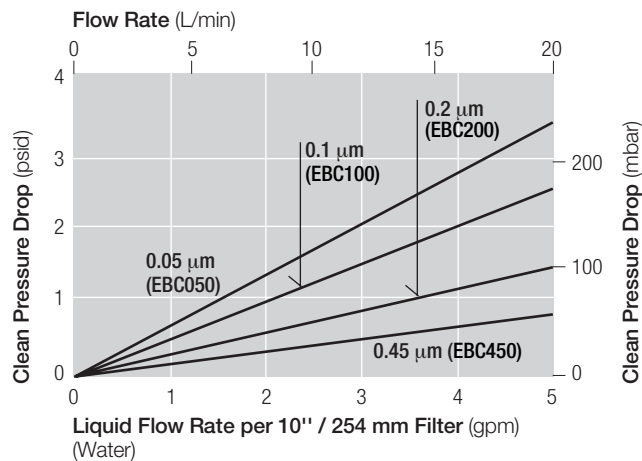
Code O-Ring Materials

V	Viton A (standard)
T	FEP Encapsulated Silicone
F	FEP Encapsulated Viton A
C	Chemraz ⁴

⁴ Chemraz is a trademark of Greene, Tweed & Co.

Unit conversion: 1 bar = 100 kilopascals

Pressure Drop vs. Liquid Flow Rate⁵



⁵ For liquids with viscosity differing from water, multiply the pressure drop by the viscosity in centipoise.

LENNTECH

info@lennotech.com

www.lennotech.com

Tel. +31-15-261.09.00

Fax. +31-15-261.62.89

Filtration. Separation. Solution.SM

Pall Corporation has offices and plants throughout the world. For Pall representatives in your area, please go to www.pall.com/contact.

Because of technological developments related to the products, systems, and/or services described herein, the data and procedures are subject to change without notice. Please consult your Pall representative or visit www.pall.com to verify that this information remains valid. Products in this document may be covered by one or more of the following patent numbers: EP 0 667 800; EP 0 982 061; EP 1 380 331; US 5,543,047; US 5,690,765; US 5,725,784; US 6,113,784; US 7,083,564; US 7,318,800.

© Copyright 2004, Pall Corporation. Pall,  are trademarks of Pall Corporation. ® Indicates a Pall trademark registered in the USA. Filtration. Separation. Solution.SM is a service mark of Pall Corporation.